

Our services

Deposition and characterization of thin films under ultra-high-vacuum (D.A.U.M. Tube)



YOUR NEEDS

- Produce devices in the form of thin layers
- Elaboration of a single layer or multilayer thin films using different techniques like PVD or ALD while remaining under ultra-high-vacuum
- Characterize your thin layers (STM, AFM, XPS, Auger)
- Take advantage of the machine park at your disposal
- You can also connect your deposit chamber to the TTO part of the D.A.U.M. Tube, giving you access to its characterization tools.

RELATED SKILLS

- Study of semiconductor or dielectric thin films
- Micro and nanofabrication processes
- Probe, control and functionalize the magnetism of matter
- Thermal and optical regulation of thin films (thermochromics)
- Electron microscopy
- X-ray diffraction
- Epitaxy
- Monolayer

OUR SOLUTIONS

While remaining in the field of ultra-high-vacuum you have access to:

- 8 thin film processing systems specialized according to the type of material: MBE, Thermal Evaporators, CVD, Cathodic Sputtering, Laser Ablation
- 8 analysis and characterization systems: Surface (RHEED, STM, AFM), Chemical (Auger Spectroscopy, XPS, UPS), Properties (Kerr Effect, Ellipsometry)
- 2 functional systems: Ion etching, annealing under field conditions

OUR REFERENCES

NIPSON
Technology

VIESSMANN
climat d'innovation


KEYWORDS

D.A.U.M., PVD, ALD, PLD, Evaporation, Ultra-High-Vacuum, SEM, Thin Films, XPS, AFM, STM

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